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Page 3/3

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FORM 1449* INFORMATION DISCLOSURE STATEMENT	Docket Number: 14434.103USWO	Application Number: UNKNOWN				
IN AN APPLICATION	Applicant: TAKEUCHI et al.					
(Use several sheets if necessary)	Filing Dare: concurrent	Group Art Unit: UNKNOWN				

		U.	S. PATENT DOCUMENTS	<u> </u>			
EXAMINER DOCUMENT NO.		DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	2005/0079659	4.14.05	DUAN et al.				
	2005/0056828	3.17.05	WADA et al.				
	6,180,956	1.30.2001	CHONDROUDIS et al.				
		FORI	EIGN PATENT DOCUME	NTS /			
	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	2004/032193	15.04.2004	VIPO /				<u></u>
	2004-111870	2004.04.08	JP			ABSTRACT	
	2004-067413	2004.03.04	JP			ABSTRACT	
	2000-260999	2000.09.22	JP			SEE IDS	
	OTHER	DOCUMENTS	(Ingluding Author, Title, Da	ite, Pertinent I	Pages, Etc.)		
	Duan et nanorib	al., High-pert	ormance thin-film trans/oi. 425, September 18,	istors using 2003, pp. 2	g semiconducte 274-278 *	or nanowires a	nd
	Morales Science	et al., Plaser Vol. 779, Janu	ablation method for the sary 9, 1998, pp. 208-211	synthesis of	crystalline sem	iconductor nan	owire:
	Lew et a	, Growth cha	racteristics of silicon nan- mplates, Journal of Cryst	owires synth al Growth V	nesized by vapo ol. 254, 2003, p	r-liquid-solid gr p. 14-22 *	owib

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EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form for next communication to the Applicant.

\*Sydetitute Disclosure Statement Form (PTO-1449)

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